FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY, DOCKET NO. 10/735,355

MI22-2457

APPLICANT: Zhongze Wang

FILING DATE December 12, 2003

GROUP 2811

U.S. PATENT DE TRANSPORTE							
Examiner's Initials		Document Number	Oate	Name	Class	Subclass	Filing Date II Appropriate
94	*	6,048,411	4/2000	Henley et al.			1
M	AB	6,071,783	6/2000	Liang et al.			
qu	AC	6,091,076	7/2000	Deteonibus			
QU	AĐ	6,245,729	2/2002	Maszara			
CM	Æ	6,346,729	2/2002	Liang et al.		•	7
GU	A.F	6,358,791	3/2002	Hsu et al. FN 54	Q F	72	105
GU	AG	6,403,485	6/2002	Quek et al.	,		
Au	AH	6,649,959	11/2003	Hsu et al.		/	
21	N	6,664,146	12/2003	Yu			
CM	۸ _	5008 0 0 0 4 2 B 4	4/2002	Sakaguchi			
M	AK	2002/0034844	3/2002	Yusukawa		7	
A	М	10/924,776		Ford			08/25/2004

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)						
$\bigcirc$	AM	Bashir et al., Characterization of sidewall defects in selective epitaxial growth of silicon, 13 J. VAC. Sci.				
4		TECHNOL. B, No. 3, pp. 923-927 (May/June 1995).				
$\bigcap$	1	Bashir et al., Reduction of sidewall defect induced leakage currents by the use of nitrided field oxides in				
90		silicon selective epitaxial growth, 18 J. Vac. Sci. Technol. B, No. 2, pp. 695-699 (March/April 2000).				
ML	AO	Hammad et al., The Pseudo-Two-Dimensional Approach to Model the Drain Section in SOI MOSFETs.				
Hr.		48 IEEE TRANSACTIONS ON ELECTRON DEVICES, No. 2, pp. 386-387 (February 2001).				
SU	ΑP	Sivagnaname et al., Stand-by Current in PD-SOI Pseudo-nMOS Circuits, IEEE, pp. 95-96 (2003)				
All	40	Wang et al., Achieving Low Junction Capacitance on Bulk SI MOSFET Using SDOI Process, Micron Technology, Inc., 12 pages (pre-2004).				
EXAMILIER DATE CONSIDERED Sugust 212, 2005						
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw tine through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.						

Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY, DOCKET NO. MI22-2457	SERIAL NO. 10/735,355		
O P E STOF	ART CITED BY APPLICANT  • several sheets if necessary)	APPLICANT: Zhongze Wang			
APR 1 4 7005 S	<i>j</i>	FILING DATE December 12, 2003	GROUP 2811		

U.S. PATENT DESCRIPTION							
Examiner's Initials		Document Number	Date	етен	Closs	Subclass	Filing Date If Appropriate
94		6,048,411	4/2000	Henley et al.			1
Qy.	AB	6,071,783	6/2000	Liang et al.			/
gu	AC	6,091,076	7/2000	Deleonibus			/
QU	AD	6,245,729	2/2002	Maszara			/
CM	Æ	6,346,729	2/2002	Liang et al.			1
JU.	AF	8,358,791	3/2002	Hsu et al. EV 54	0 4	72	105
Pu	AG	6,403,485	6/2002	Quek et al.	70	16/	4 A 🐴
Au	AH	6,649,959	11/2003	Hsu et al.			
21	N	6,664,146	12/2003	Yu			
M	٧_	5000 000 48 <b>6</b> 4	4/2002	Sakaguchi		/	
MI	AK	2002/0034844	3/2002	Yusukawa		1	
	. 44	10/924,776		Ford			08/25/2004

OTIFO DESCRIPTION AND ADDRESS OF THE PROPERTY						
OTHER REFERENCES (including Author, Title, Date, Pertinant Pages, Etc.)						
$\bigcap$	, AM	Bashir et al., Characterization of sidewall defects in selective epitaxial growth of silicon, 13 J. VAC. Sci.				
4		TECHNOL. B, No. 3, pp. 923-927 (May/June 1995).				
$\bigcap_{\lambda}$	1 4	Bashir et al., Reduction of sidewall defect induced leakage currents by the use of nitrided field oxides in				
70		silicon selective epitaxial growth, 18 J. Vac. Sci. Technol. B, No. 2, pp. 695-699 (March/April 2000).				
ML	AO	Hammad et al., The Pseudo-Two-Dimensional Approach to Model the Drain Section in SOI MOSFETs,				
The state of the s		48 IEEE TRANSACTIONS ON ELECTRON DEVICES, No. 2, pp. 386-387 (February 2001).				
Su	45	Sivagnaname et al., Stand-by Current in PD-SOI Pseudo-nMOS Circuits, IEEE, pp. 95-96 (2003)				
All	مه	Wang et al., Achieving Low Junction Capacitance on Bulk SI MOSFET Using SDOI Process, Micron Technology, Inc., 12 pages (pre-2004).				
EXAMINER DATE CONSIDERED/ LUMB AUGUST 211, 2005						
"EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.						